

In place of PTO-1449 Form		U. S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		Complete if Known		10/519644	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Application Number	National Phase of PCT/GA2003/000960		
				Filing Date	Harwith 08/15/2005		
				Applicant(s)	Alicja Zaluska, et al.		
				Art Unit	Unknown 1756 1755		
				Examiner Name	Unknown Hailey		
SHEET	1	OF	1	Attorney Docket Number	25000-24		

U. S. PATENT DOCUMENTS				
Examiner's Initials	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
/LH/	A1	4,368,143	01/11/1983	Olivier de Pous
/LH/	A2	4,507,263	03/26/1985	Moshe Ron
/LH/	A3	6,251,349	06/26/2001	Alicja Zaluska et al.
/LH/	A4	6,342,318	01/29/2002	Shin Fujitani et al.

FOREIGN PATENT DOCUMENTS					
Examiner's Initials	Cite No.	Foreign Patent Document (Country Code - Number - Kind)	Publication Date MM-DD-YYYY	Patentee or Applicant of Cited Document	Translation Y/N
/LH/	A5	WO 00/07930 A	02/17/2000	University of Hawaii	

NON-PATENT LITERATURE DOCUMENTS		
Examiner's Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article, title of the item, date, page(s), volume- issue number(s), publisher, city/country where published
/LH/	A6	OELERICH W. ET AL.; <i>Metal oxides as catalysts for improved hydrogen sorption in nanocrystalline Mg-based materials</i> ; Journal of Alloys and Compounds, Elsevier Sequoia, Lausanne, CH; vol. 315, 2001, pages 237-242
/LH/	A7	OELERICH W. ET AL.; <i>Comparison of the catalytic effects of V, V2O5, VN, and VC on the hydrogen sorption of nanocrystalline Mg</i> ; Journal of Alloys and Compounds, Elsevier Sequoia, Lausanne, CH; vol. 322, no. 1-2; June 28, 2001, pages L5-L9

Examiner Signature	/Patricia Hailey/	Date Considered	09/13/2007
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